

Supplementary material for

Enhanced electrically and thermally conductive free-standing graphene films with two-dimensional copper nanosheets as catalyst and bridge

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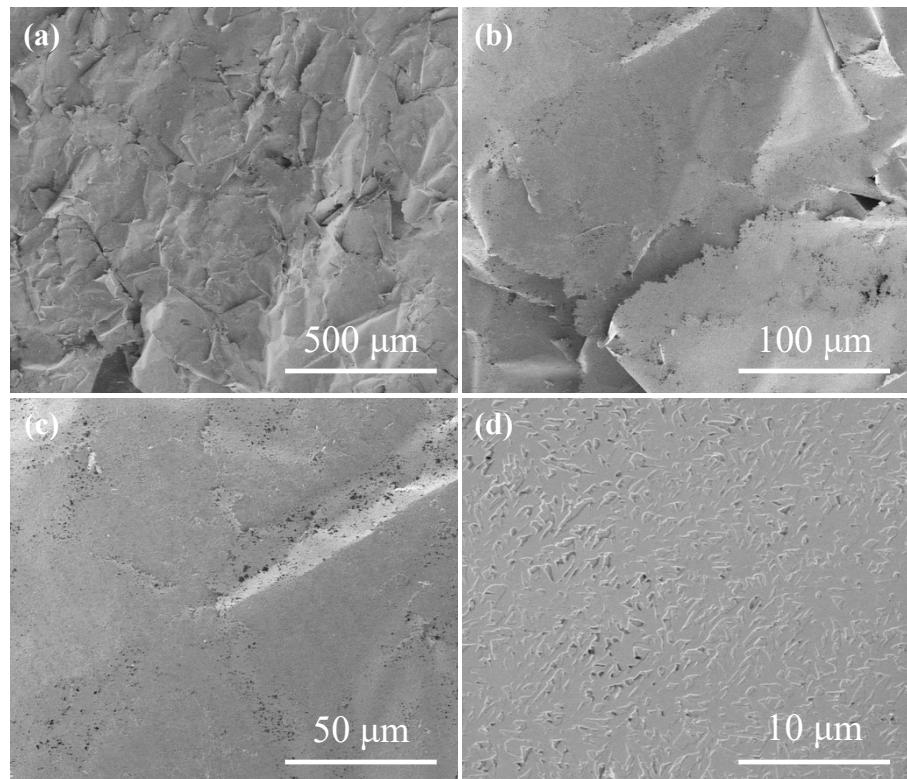


Fig. S1 SEM images of the as-prepared two-dimensional copper under different magnifications.

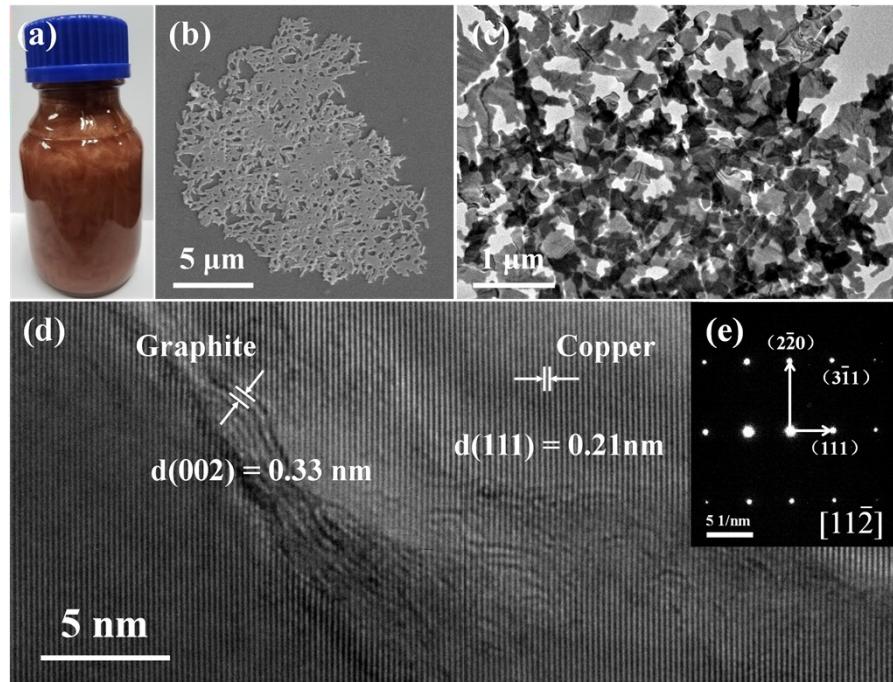


Fig. S2 (a) Optical, (b) SEM, and (c, d) HRTEM images of the two-dimensional copper after a certain dispersion process. (e) Selected area electron diffraction analysis of (d).

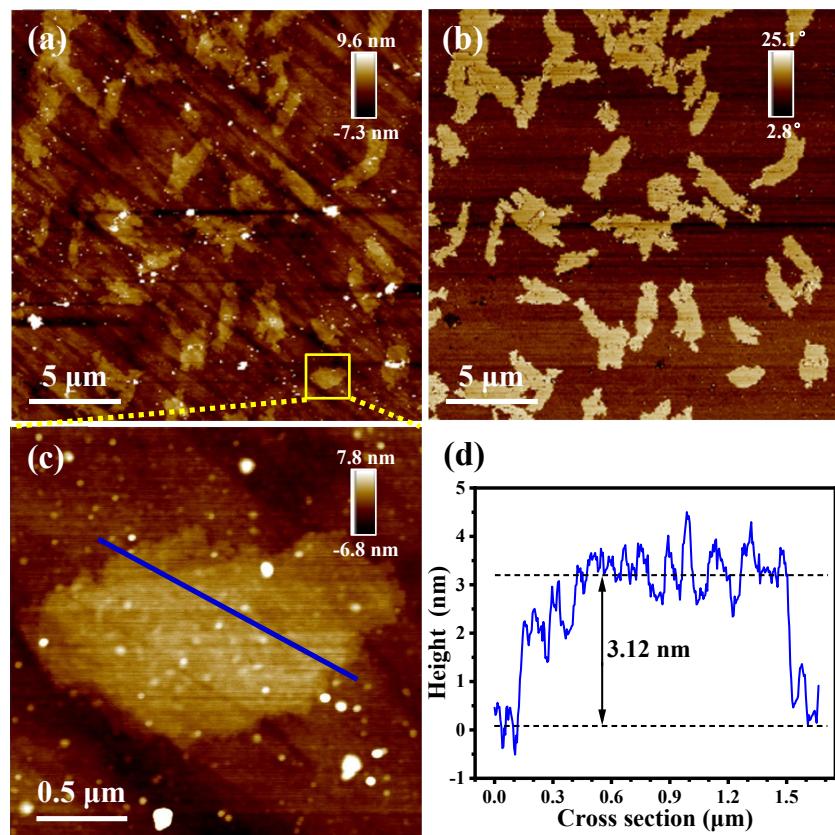


Fig. S3 AFM characterizations of the as-prepared copper after dispersion: (a, c) height and (b) phase images; (d) height profiles of a typical two-dimensional structure in (c).

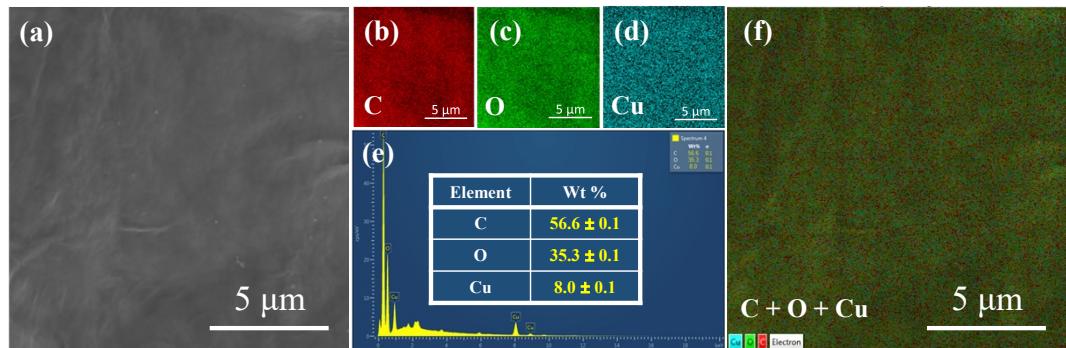


Fig. S4 Typical (a) SEM and (b–f) SEM–EDS mapping images of Cu/GO films.

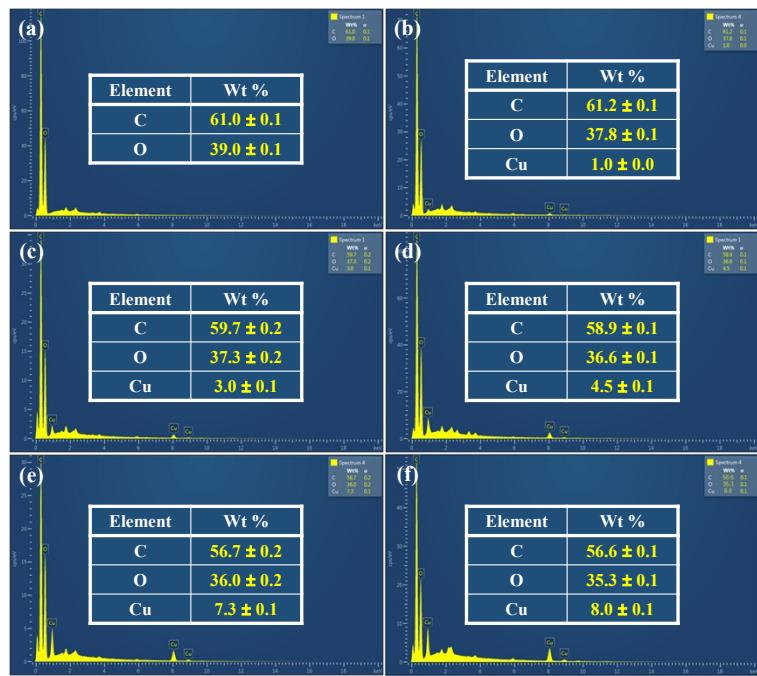


Fig. S5 Elemental content analysis via SEM-EDS: (a) GO; (b) Cu/GO-1; (c) Cu/GO-2; (d) Cu/GO-3; (e) Cu/GO-4; and (f) Cu/GO-5.

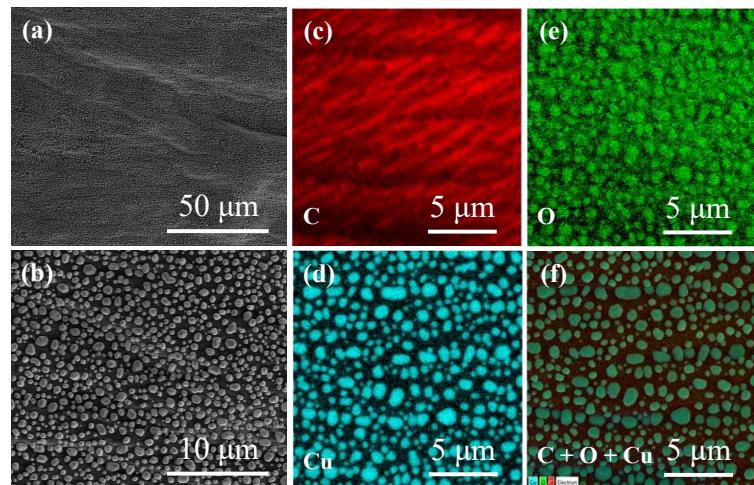


Fig. S6 (a, b) SEM images and (c-f) SEM-EDS mapping images of the Cu/rGO film prepared through annealing at 1000 °C.

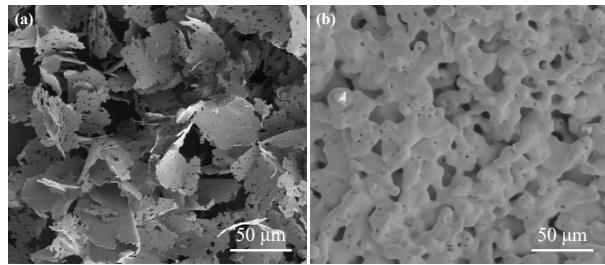


Fig. S7 SEM images of the two-dimensional copper after annealing at (a) 900 and (b) 1000 °C.

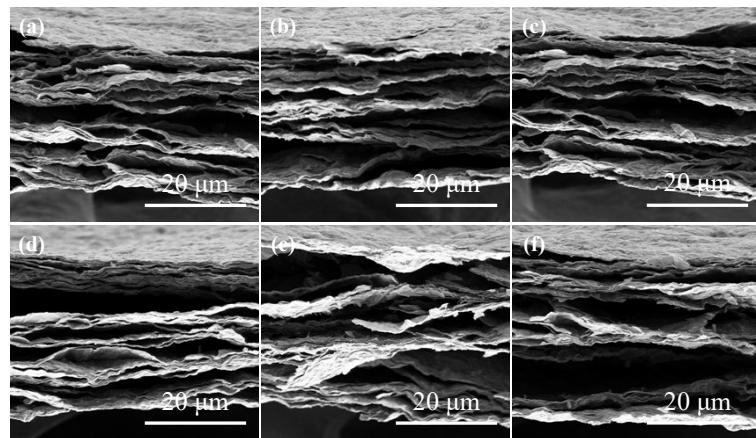


Fig. S8 SEM images of the cross-sections of the as-prepared films: (a) rGO; (b) Cu/rGO-1; (c) Cu/rGO-2; (d) Cu/rGO-3; (e) Cu/rGO-4; and (f) Cu/rGO-5.

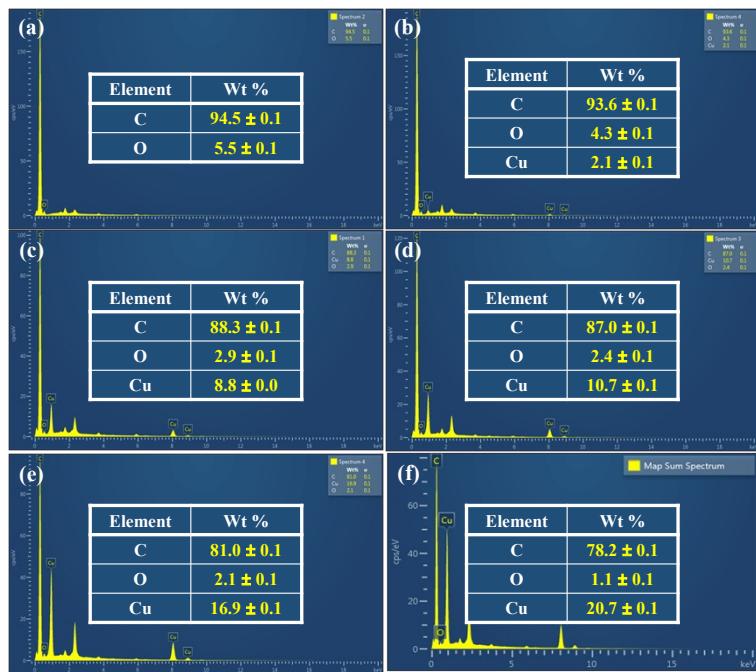


Fig. S9 Elemental content analysis through SEM-EDS: (a) rGO; (b) Cu/rGO-1; (c) Cu/rGO-2; (d) Cu/rGO-3; (e) Cu/rGO-4; and (f) Cu/rGO-5.

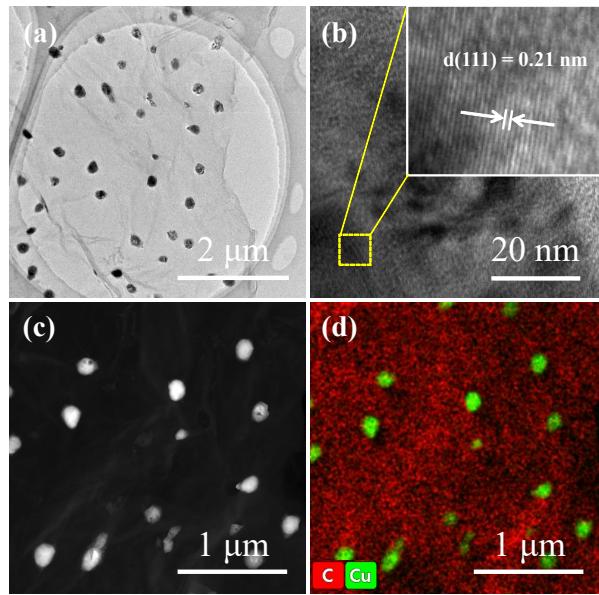


Fig. S10 (a, b) HRTEM, (c) HAADF-STEM, and (d) HAADF-STEM-EDS mapping images of typical Cu/rGO.

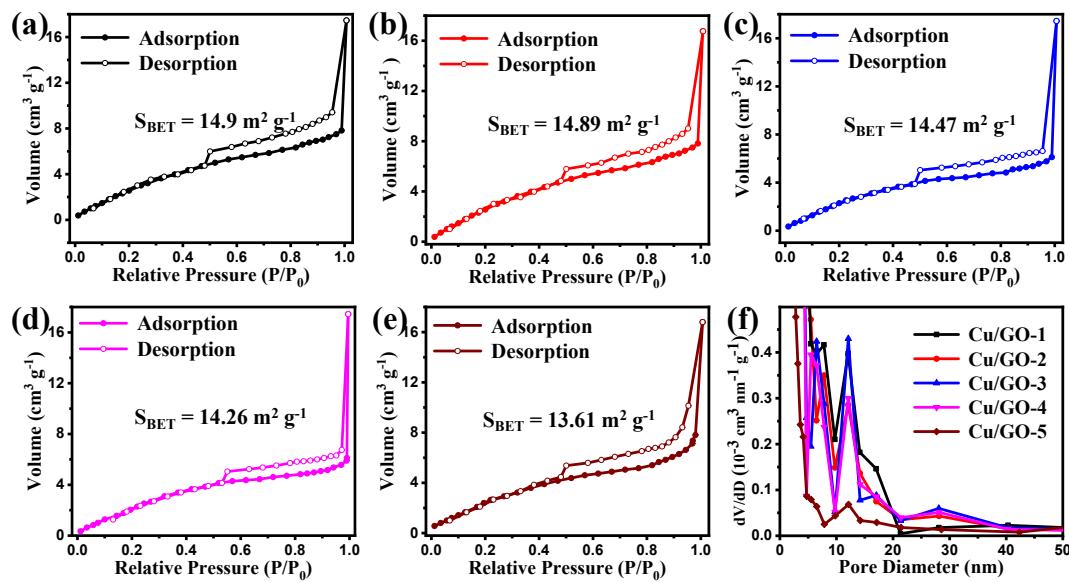


Fig. S11 Nitrogen adsorption-desorption isotherms of (a) Cu/GO-1, (b) Cu/GO-2, (c) Cu/GO-3, (d) Cu/GO-4, (e) Cu/GO-5, and corresponding (e) pore size distributions.

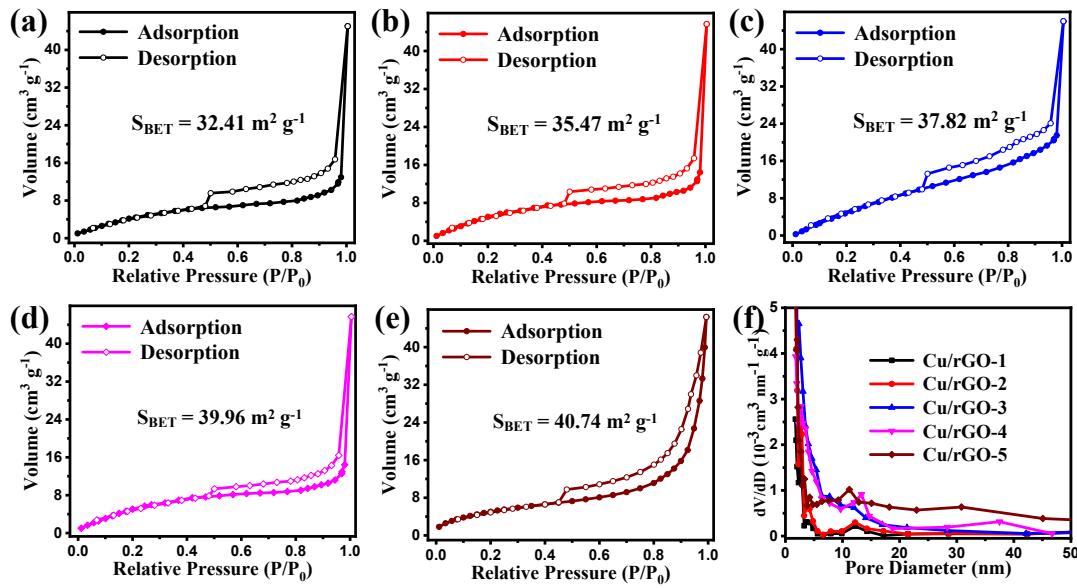


Fig. S12 Nitrogen adsorption-desorption isotherms of (a) Cu/rGO-1, (b) Cu/rGO-2, (c) Cu/rGO-3, (d) Cu/rGO-4, (e) Cu/rGO-5, and corresponding (e) pore size distributions.

Table S1 Comparative summary of thermal conductivity of graphene-based composite films.

| Films | Fabrication Method | Reduction Method Post-Treatment | Thermal Measurement t | Thermal conductivity (W m⁻¹ K⁻¹) | Refer. |
|----------|---------------------------|-----------------------------------|-----------------------|----------------------------------|-----------|
| Cu/rGO | Vacuum filtration | Annealed at 900 °C for 2 h | Laser flash | 859 | This work |
| N-Gr | Vacuum filtration | Annealed at 800 °C for 8 h | Laser flash | 542.9 | 1 |
| Gr/Cu/Gr | Chemical vapor deposition | / | Laser flash | 376.4 | 2 |
| rGO | Vacuum filtration | graphitization at 2600 °C for 4 h | Laser flash | 803.1 | 3 |
| Graphene | Vacuum filtration | dried at 105 °C for 3 h | Laser flash | 112 | 4 |
| Graphite | Vacuum filtration | annealed at 340 °C for 2 h | Laser flash | 190 | 5 |

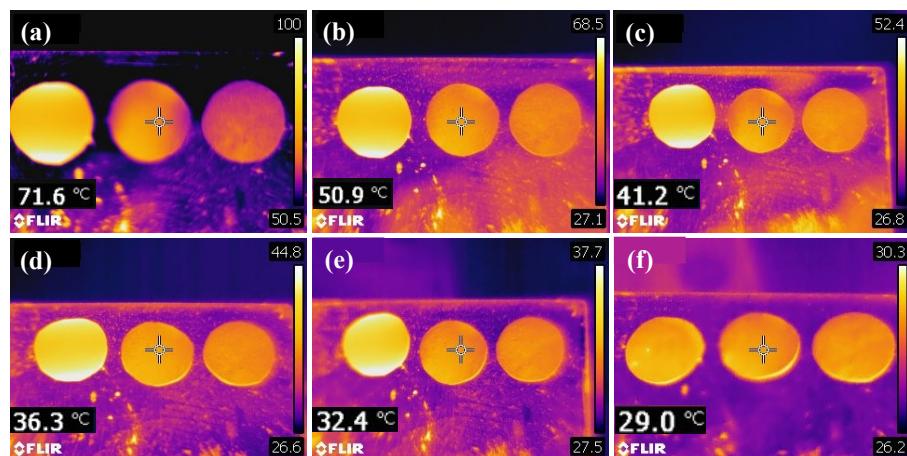


Fig. S13 Infrared thermal images of graphene films under different time: (a) 20 s, (b) 40 s, (c) 60 s, (d) 80 s, (e) 100 s, and (f) 120 s.

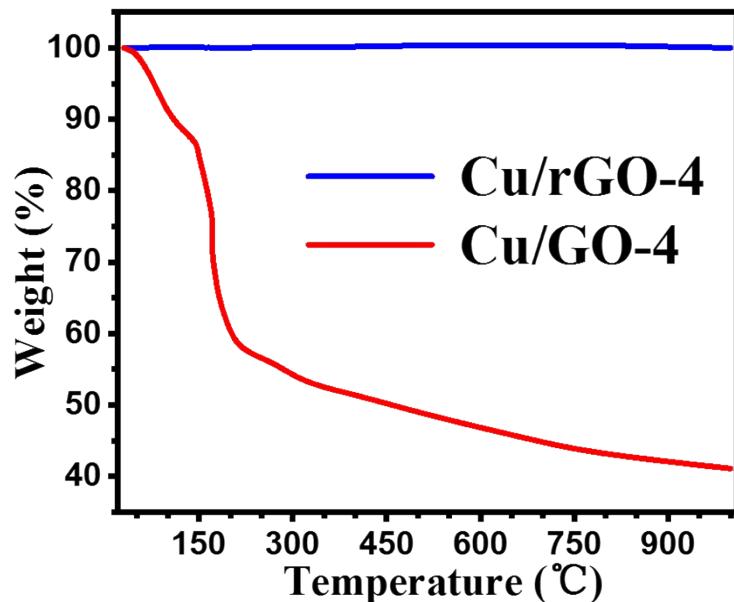


Fig. S14 TGA curves of Cu/GO-4 and Cu/rGO-4.

References

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